



# Graphene and two-dimensional materials

Gianluca Fiori, Giuseppe Iannaccone,

Dipartimento di Ingegneria dell'Informazione  
Università di Pisa



# The scaling context

## Transistor Innovations Enable Technology Cadence

2003



Invented  
SiGe  
Strained Silicon

2005



2<sup>nd</sup> Gen.  
SiGe  
Strained Silicon

2007



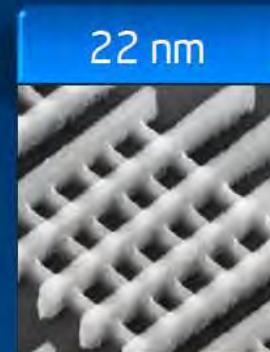
Invented  
Gate-Last  
High-k Metal Gate

2009



2<sup>nd</sup> Gen.  
Gate-Last  
High-k Metal Gate

2011



First to  
Implement  
Tri-Gate

Strained Silicon

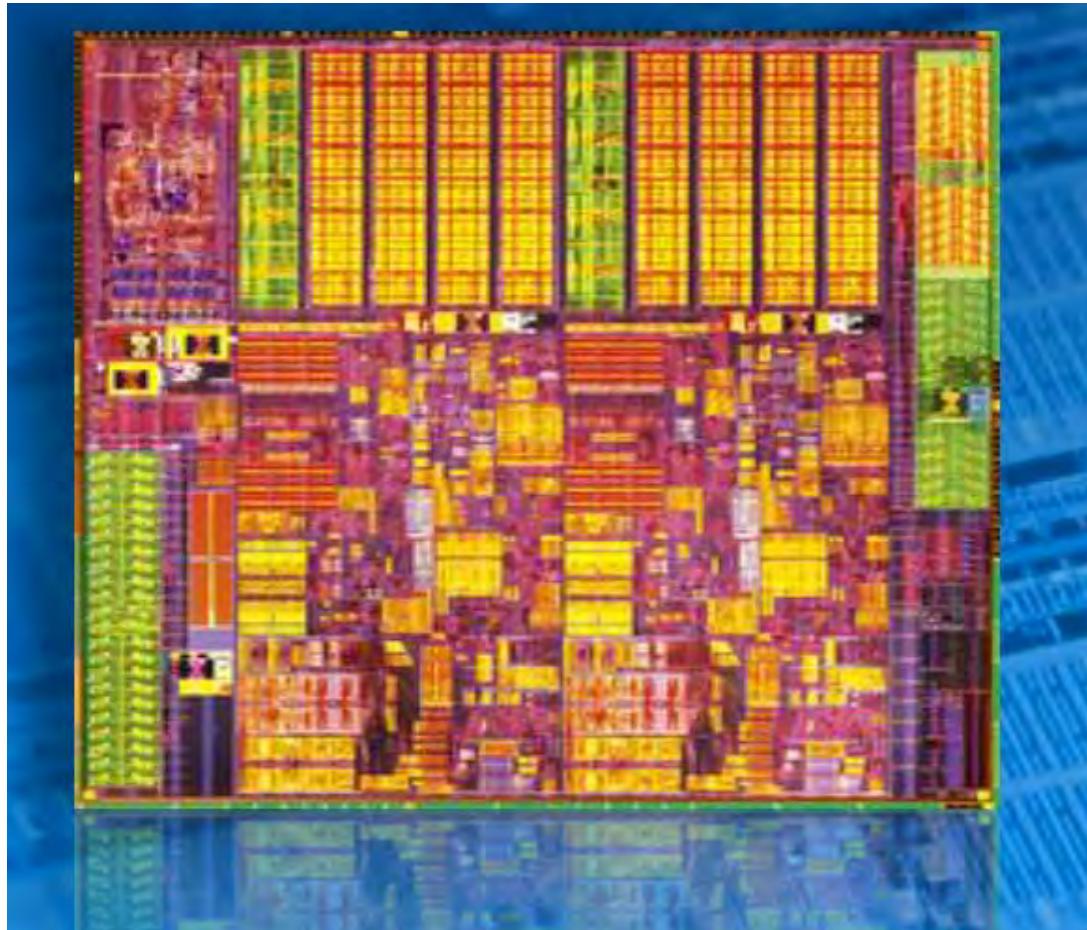
High k Metal gate

Tri-Gate





# And now?



2013  
22 nm process  
1B transistor



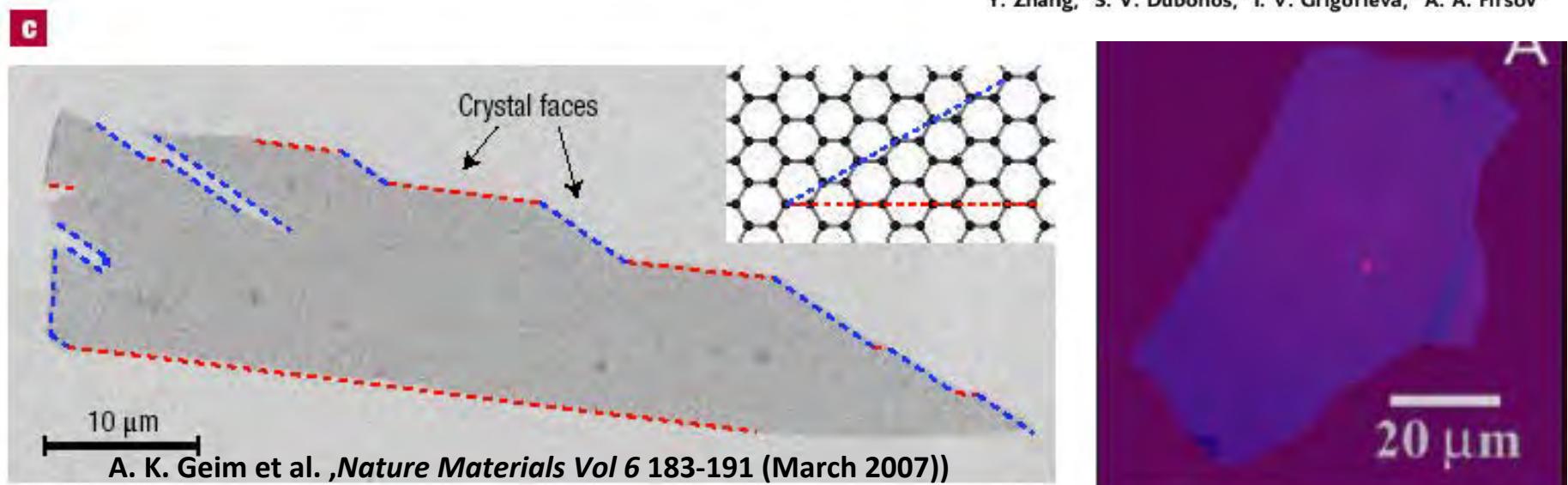
# Graphene

22 OCTOBER 2004 VOL 306 SCIENCE www.sciencemag.org

<sup>2D</sup><sup>3</sup>Allotrope: N.S. Novoselov 2004 [K.S. Novoselov et al., Science, 306, 5696,2004].

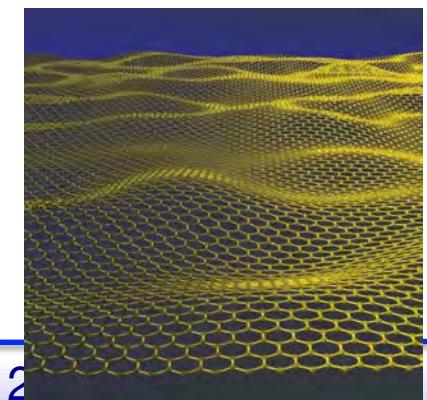
## Electric Field Effect in Atomically Thin Carbon Films

K. S. Novoselov,<sup>1</sup> A. K. Geim,<sup>1\*</sup> S. V. Morozov,<sup>2</sup> D. Jiang,<sup>1</sup> Y. Zhang,<sup>1</sup> S. V. Dubonos,<sup>2</sup> I. V. Grigorieva,<sup>1</sup> A. A. Firsov<sup>2</sup>



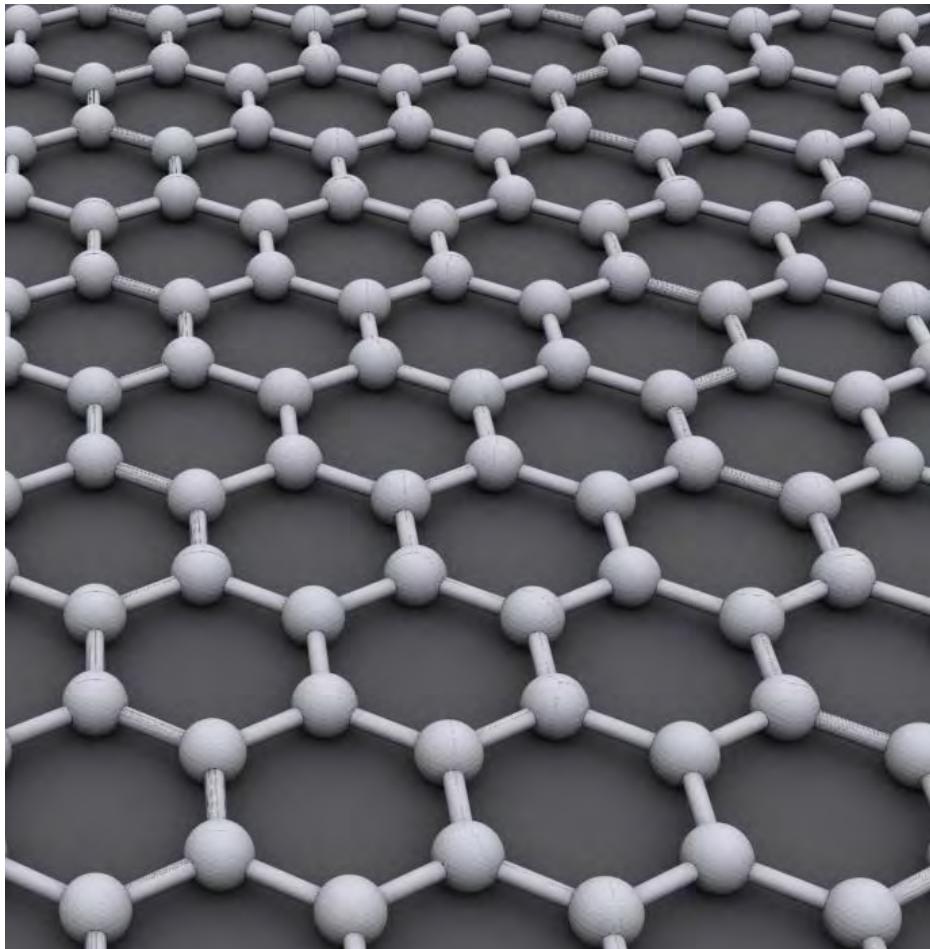
- K. Novoselov et al., Science 306, 666, 2004.
- K. Novoselov et al., Nature 438, 197, 2005.
- K. Novoselov et al., Nature Physics 2, 177, 2006.

*Image: Jannik Meyer*  
[http://faraday.fc.up.pt/.../admin/copy\\_of teste/image](http://faraday.fc.up.pt/.../admin/copy_of teste/image)





# Graphene as a material for electronics



- High mobility at room temperature ( $>10^4 \text{ cm}^2/\text{Vs}$ )
- Symmetric properties for electrons and holes
- One-atom thin -> promising for scaling
- Cheap and CMOS compatible ....but ....  
... the zero energy gap is a showstopper for use in (digital) electronics ....



## Rules of the game

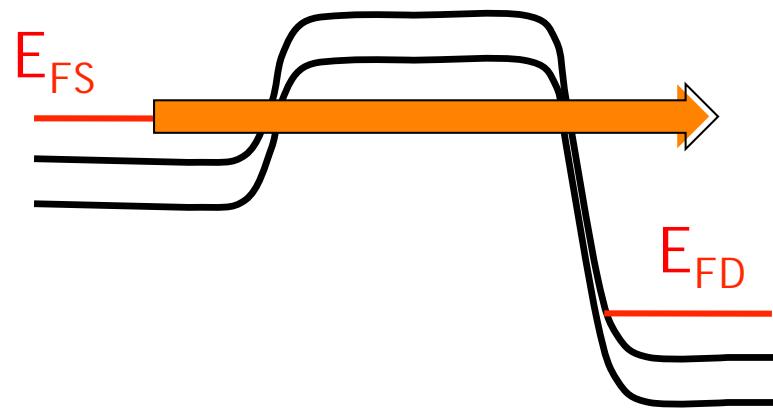
Increase gap, fabricate device, but  
keep mobility high, keep reproducibility high



# Energy gap and the Off state

Poor off state

source    channel    drain



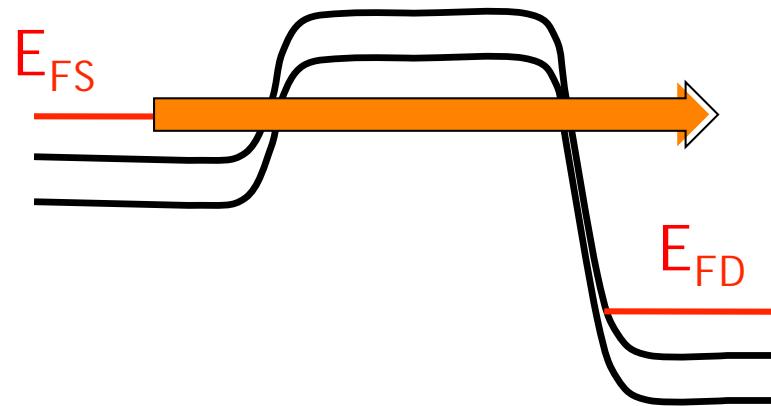
Small energy gap enables  
interband leakage => **high  $I_{off}$**



# Energy gap and the Off state

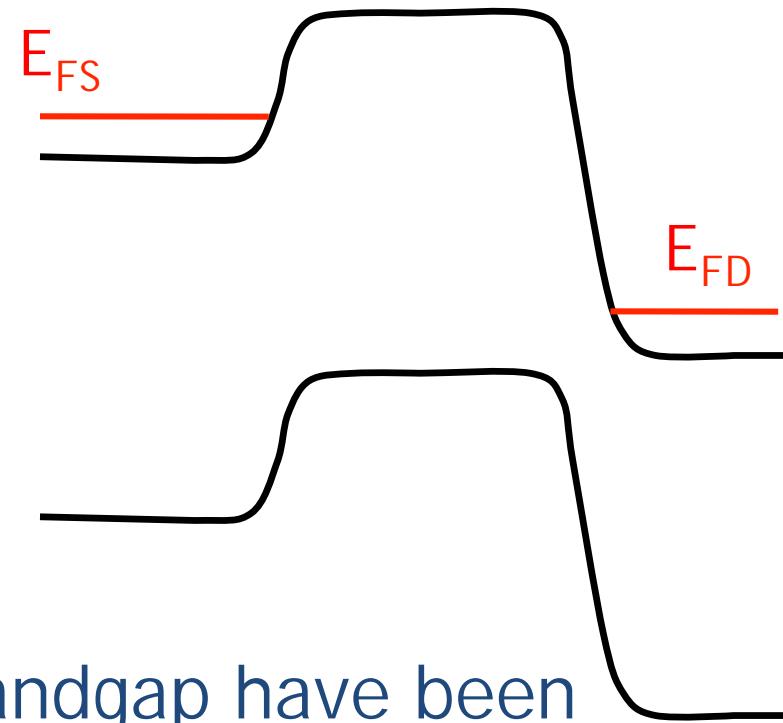
Poor off state

source channel drain



Good off state

source channel drain



Small energy gap enables  
interband leakage => **high  $I_{off}$**

Several options to induce a bandgap have been pursued → manufacturability challenges



# Device modeling tool: NanoTCAD VIDES

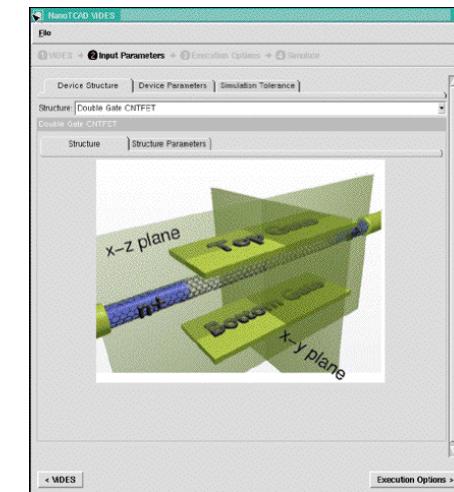
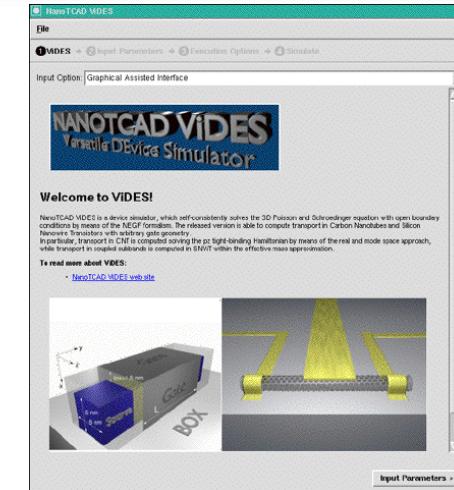
3D Non-Equilibrium Green's Functions (NEGF) solver

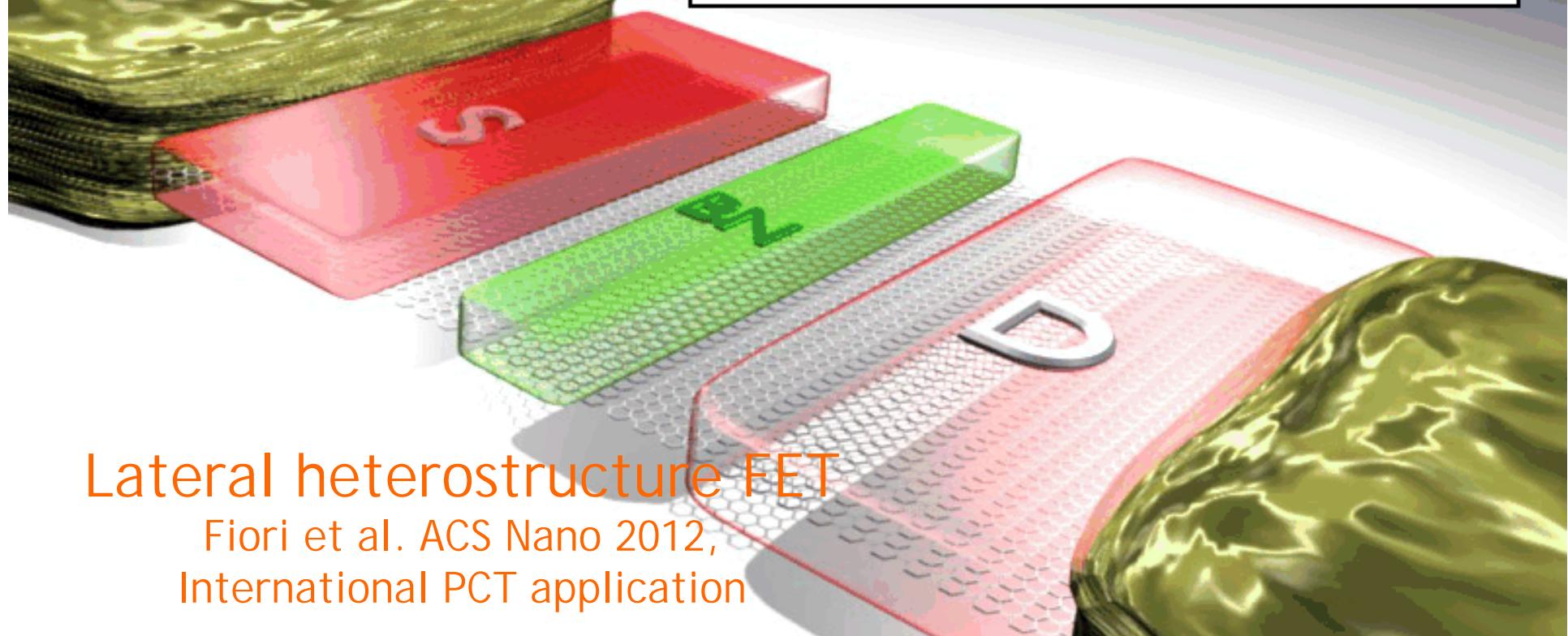
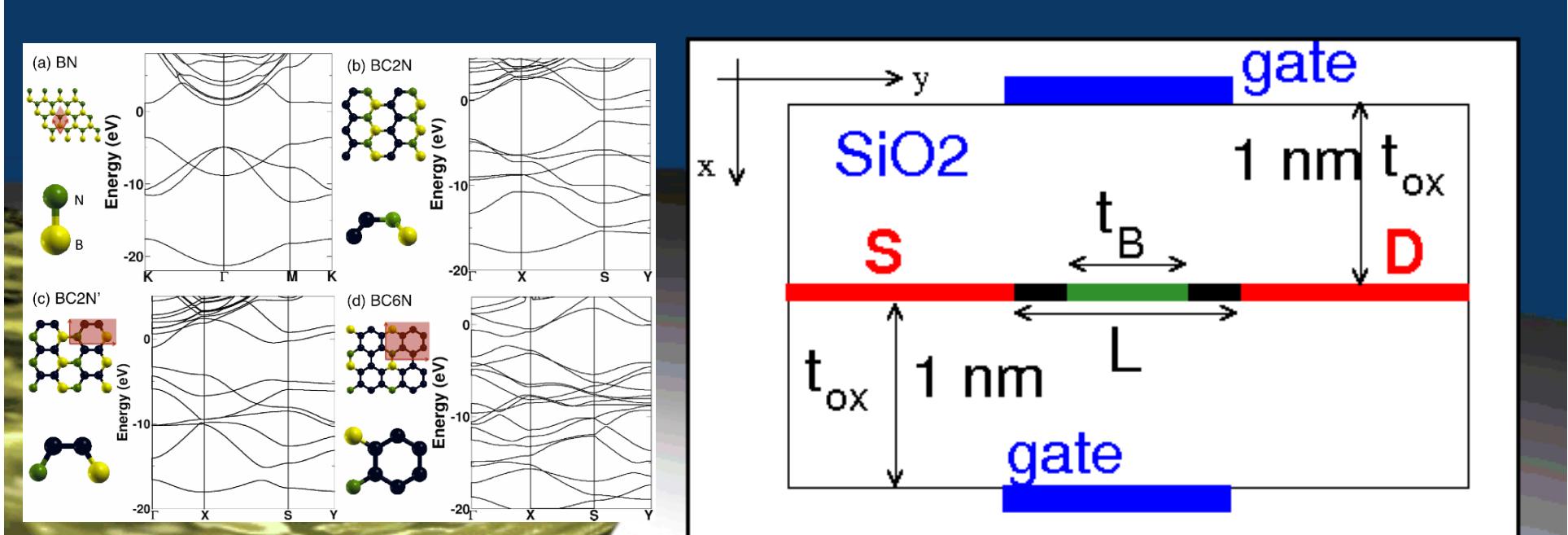
Fully coherent transport

Generic 3D structures

- CNT and GNR FETs (TB atomistic)
- Bilayer graphene FETs (TB atomistic)
- Semiconductor NW Transistors (**EMA** + TB atomistic)
- hBCN

New version of the code as a **python module** - all documentation and code at: <http://vides.nanotcad.com> and on the [nanohub.org](http://nanohub.org) → More than 300 downloads





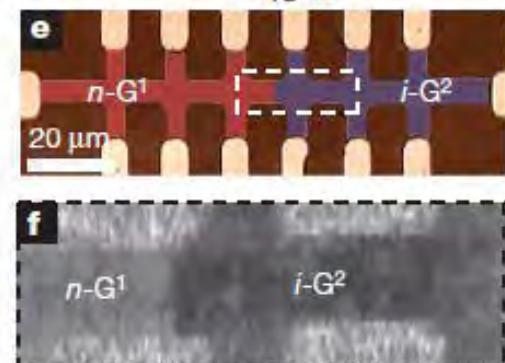
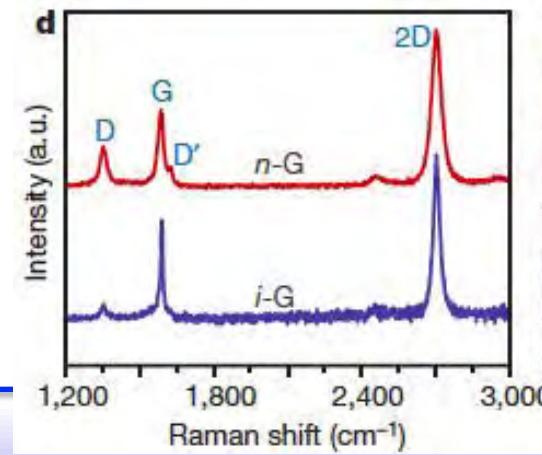
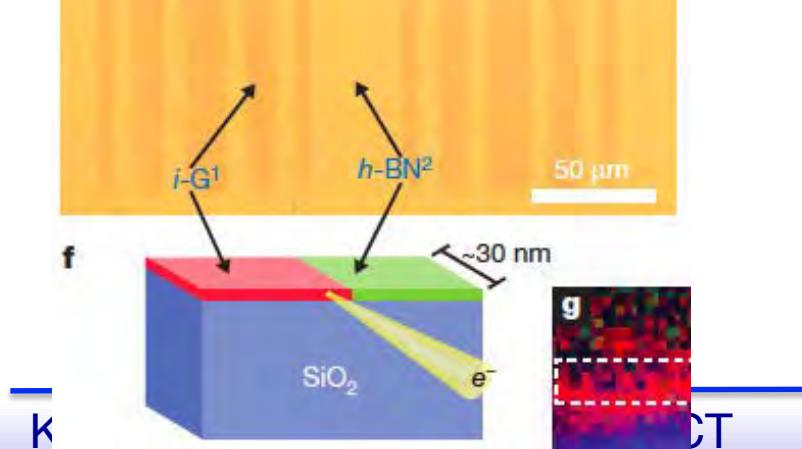
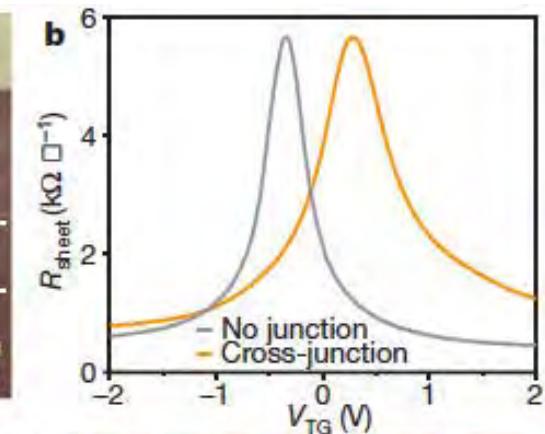
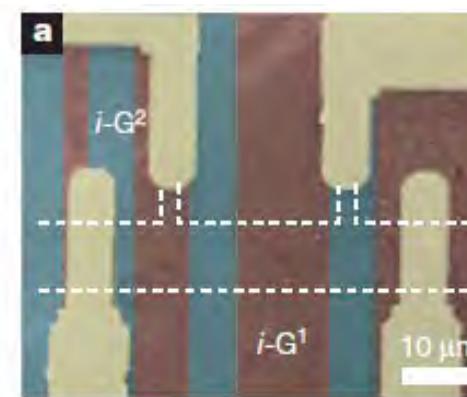
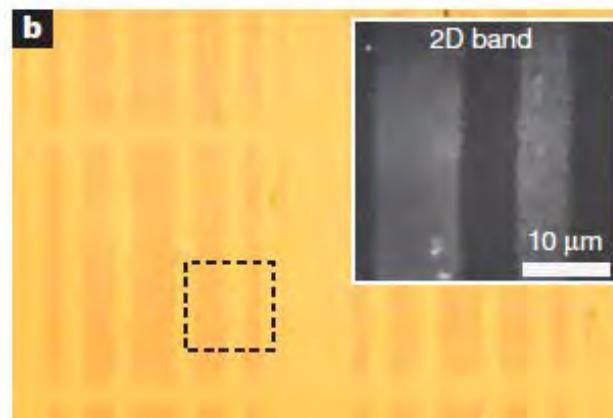
## Lateral heterostructure FET

Fiori et al. ACS Nano 2012,  
International PCT application



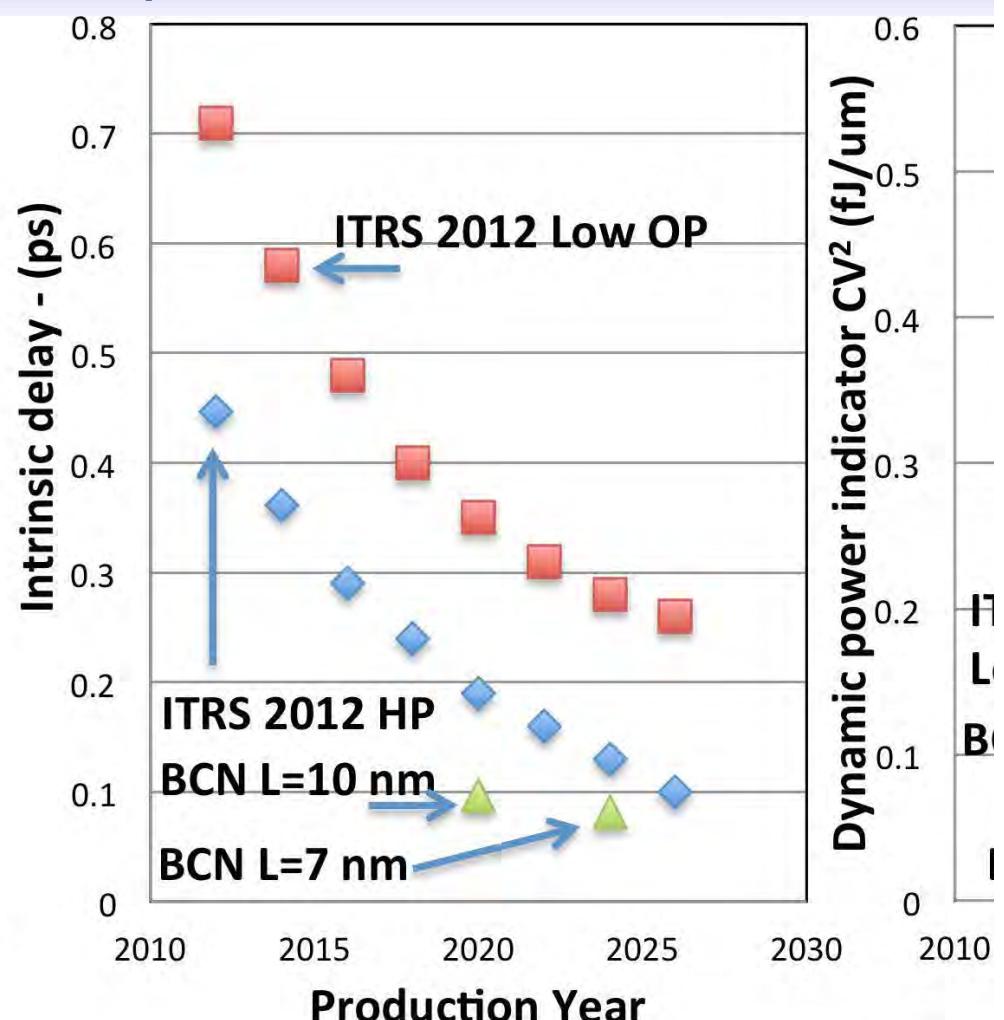
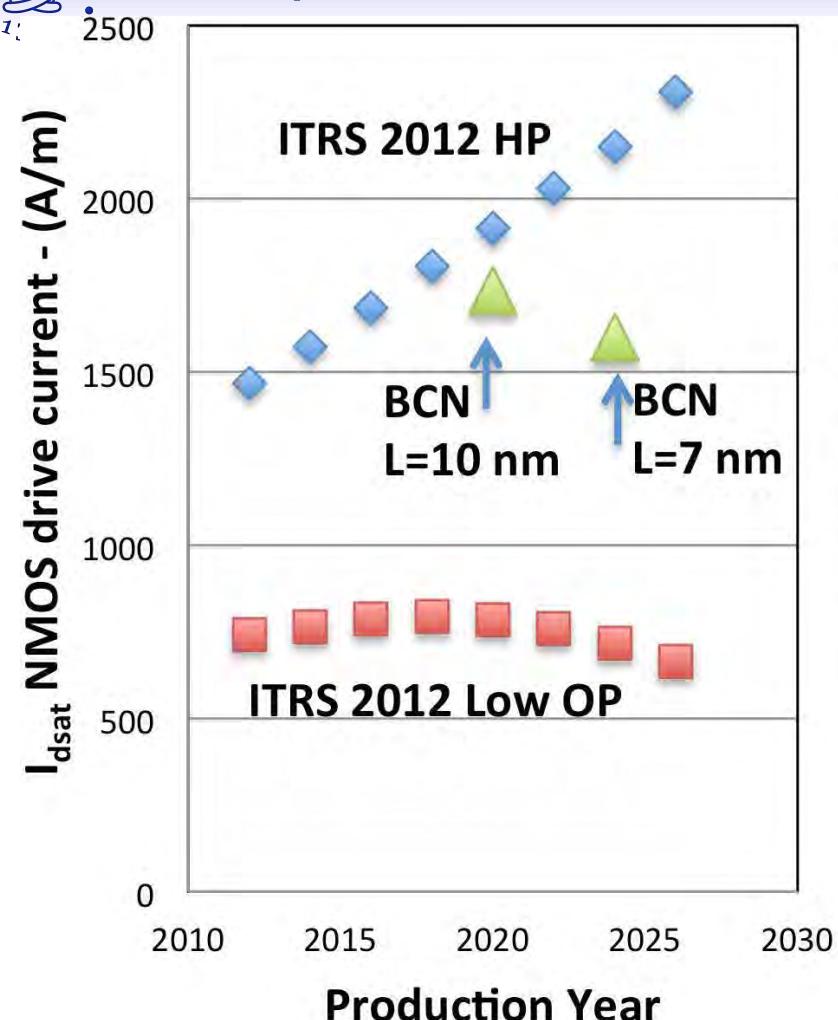
ures

M.P. Levendorf  
Nature 2012  
(Cornell)



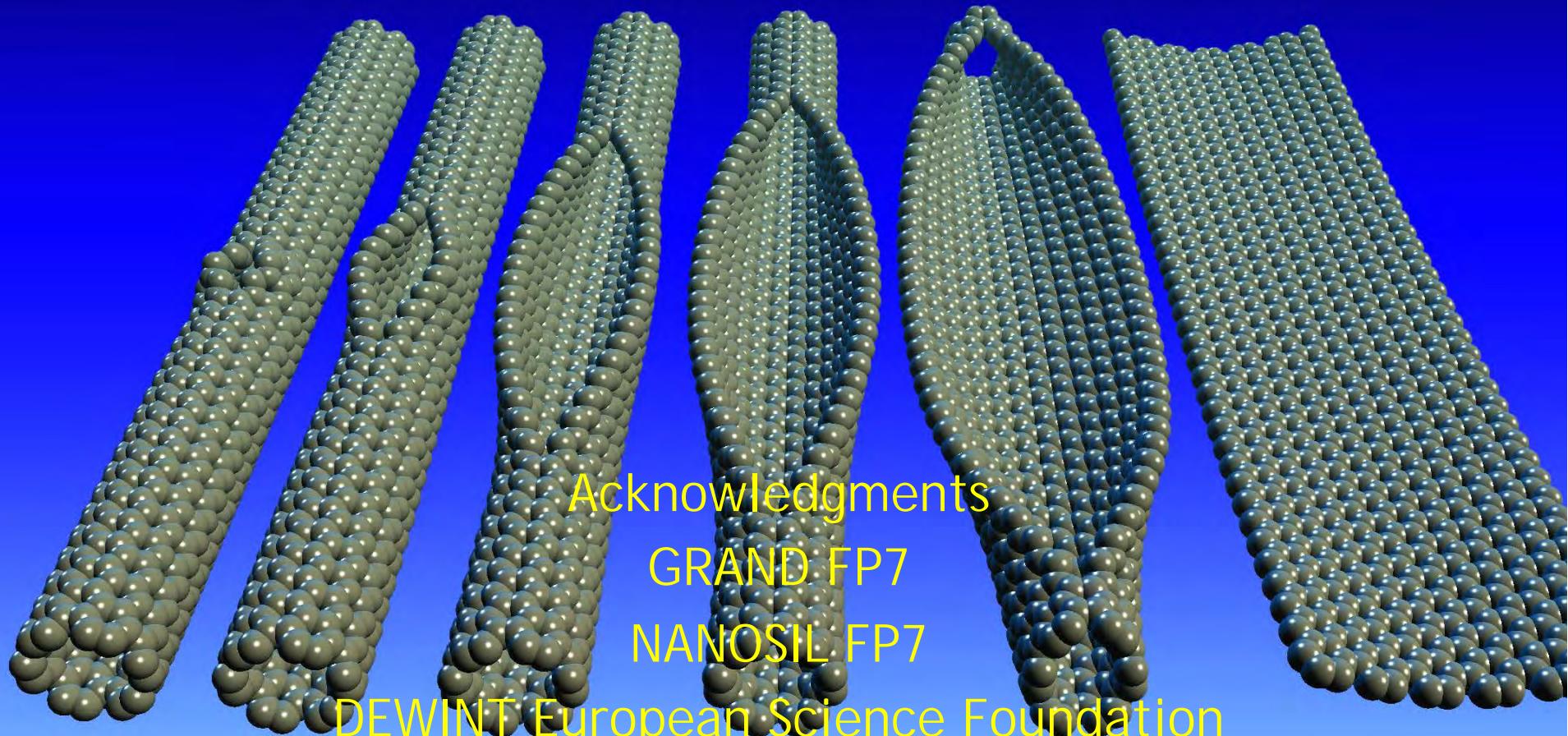


# Graphene LHFET - Comparison with ITRS 2012



$I_{off}$  fixed at 100 nA/ $\mu\text{m}$  (as for HP) [Low OP has  $I_{off}$  5 nA/ $\mu\text{m}$ ]

# Thank you



Acknowledgments

GRAND FP7

NANOSIL FP7

DEWINT European Science Foundation

GONEXTS FP7

GRADE FP7